WEST Search History

| Hide Items | Restore | Clear | Cancel |

DATE: Monday, February 13, 2006

Hide?	Set Name	Query	Hit Count
		DB=EPAB,JPAB,DWPI,TDBD; PLUR=YES; OP=ADJ	
⌐	L7	L6 same ((chamber or apparatus) adj5 (clean$3 or etch$3 or treat$3))	62
⌐	L6	(semiconductor or substrate or workpiece or wafer) with (clean$3 or treat$3 or etch$3) with (hydrogen or 'H.sub.2') with plasma	722
		DB=PGPB,USPT,USOC; PLUR=YES; OP=ADJ	
⌐	L5	L4 and l3	10
⌐	L4	134/1,1.3,21,21.1,26,30,902;438/905,906.ccls.	8260
⌐	L3	l2 with argon	197
⌐	L2	(semiconductor or substrate or workpiece or wafer) with (clean$3 or treat$3 or etch$3) with (hydrogen or 'H.sub.2') with plasma	1542
⌐	L1	(semiconductor or substrate or workpiece or wafer) with (clean$3 or treat$3 or etch$3) with (hydrogen or 'H.sub.2O' with plasma)	8361

END OF SEARCH HISTORY

WEST Search History

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DATE: Monday, February 13, 2006

Hide?	Set Name	Query	Hit Count
		DB=PGPB,USPT,USOC,EPAB,JPAB,DWPI; PLUR=YES; OP=ADJ	
☐	L17	L16 and (((probe or transmit$3 or transduc$3) with vibrat$3 with energ$5) same ((wafer or substrate or workpiece) with rotat$3))	3
☐	L16	L15 or l14 or l13 or l12 or l11 or l10	142227
☐	L15	(samsung electronics co).as.	141369
☐	L14	jo-hyun$.in.	38
☐	L13	nam-jeong$.in.	90
☐	L12	kim-kyung$.in.	967
☐	L11	yoon-byoung$.in.	53
☐	L10	yeo-in$.in.	86
		DB=USPT,USOC; PLUR=YES; OP=ADJ	
☐	L9	((probe or transmit$3 or transduc$3) with vibrat$3 with energ$5) same ((wafer or substrate or workpiece) with rotat$3)	28
		DB=PGPB; PLUR=YES; OP=ADJ	
☐	L8	((probe or transmit$3 or transduc$3) with vibrat$3 with energ$5) same ((wafer or substrate or workpiece) with rotat$3)	10
		DB=PGPB,USPT,USOC; PLUR=YES; OP=ADJ	
☐	L7	((probe or transmit$3 or transduc$3) with vibrat$3 with energ$5) same ((wafer or substrate or workpiece) with rotat$3)	38
		DB=EPAB,JPAB,DWPI,TDBD; PLUR=YES; OP=ADJ	
☐	L6	((probe or transmit$3 or transduc$3) with vibrat$3 with energ$5) same ((wafer or substrate or workpiece) with rotat$3)	2
☐	L5	((probe or transmit$3 or transduc$3) with vibrat$3) same ((wafer or substrate or workpiece) with rotat$3)	45
☐	L4	probe with vibrat$3 with (wafer or substrate or workpiece) with rotat$3	0
		DB=USPT,USOC; PLUR=YES; OP=ADJ	
☐	L3	probe with vibrat$3 with (wafer or substrate or workpiece) with rotat$3	14
		DB=PGPB; PLUR=YES; OP=ADJ	
☐	L2	probe with vibrat$3 with (wafer or substrate or workpiece) with rotat$3	12
		DB=USPT; PLUR=YES; OP=ADJ	
☐	L1	6039059.pn.	1

END OF SEARCH HISTORY